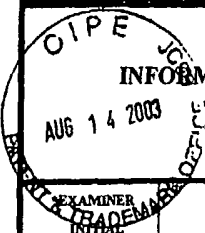


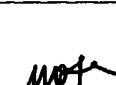
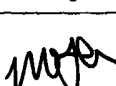
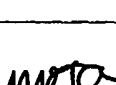
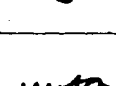
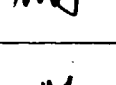
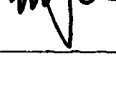
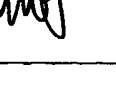
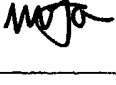
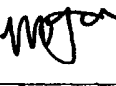
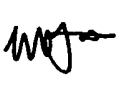
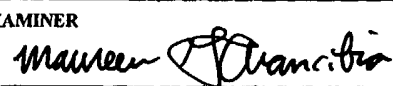
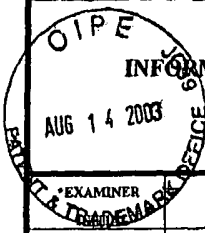


<p>OFFICE OF THE SECRETARY OF COMMERCE</p> <p>INFORMATION DISCLOSURE CITATION</p> <p>AUG 14 2003 (Use several sheets if necessary)</p>		Docket Number (Optional)	Application Number
		FIS920020166US1	10/604,487
		Applicant(s)	
Hendrik F. Hamann et al.		Filing Date	Group Art Unit
07/25/2003		1763	
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)			
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maureen Thandrea		09/13/2004	
<p>*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p>			

<div style="text-align: center;">  <p>INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)</p> </div>		Docket Number (Optional) FIS920020166US1	Application Number 10/604,487
		Applicant(s) Hendrik F. Hamann et al.	
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EXAMINER 		DATE CONSIDERED 09/13/2004	
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		Applicant(s) Hendrik F. Hamann et al.			
		Filing Date 07/25/2003		Group Art Unit 1763	
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<i>mja</i>		Maskless Lithography Using Scanning Probes, Kathryn Sara Wilder, GL report No. 5670, Edward L. Ginzton Lab., Stanford University, August 1999.			
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<i>mja</i>		Direct Writing of Metallic Nanostructures with the Scanning Tunneling Microscope, A.L.de Lozanne et al., Dept. of Physics, The University of Texas, Austin, Texas.			
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<i>mja</i>		Fabrication and Characterization Using Scanned Nanoprobes, G.C. Wetsel, Jr., Erik Jonsson School of Engineering and Computer Sciences, The University of Texas at Dallas, Richardson, Texas.			
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EXAMINER <i>Mameen Phancibia</i>		DATE CONSIDERED <i>09/13/2004</i>			
<p>*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p>					

ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

Title of Invention

SYSTEM AND METHODS OF ALTERING A VERY SMALL
SURFACE AREA

Application Number : 10/604,487
Confirmation Number:
First Named Applicant: Hendrik Hamann
Attorney Docket Number: FIS920020166US1
Art Unit: 1763
Examiner: MAUREEN G. ARANCIBIA
Search string: (4550257 or 4925139 or 5865978 or 6002471 or 4880496 or 6078055).pn

US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
WFO	1	4550257	1985-10-29	Binnig et al.			
WFO	2	4925139	1990-05-15	McCord			
WFO	3	5865978	1999-02-02	Cohen			
WFO	4	6002471	1999-12-14	Quake			
WFO	5	4880496	1989-11-14	Nevenzahl, et al.			
WFO	6	6078055	2000-06-20	Bridger, et al.			

Signature

Examiner Name	Date
Maureen G. Arancibia	09/13/2004